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PATENT NUMBER and
ISSUE DATE

U.S. UTILITY Patent Application

10035

APPL NUM 10001358	FILING DATE 10/24/2001	CLASS 438	SUBCLASS 745	GAU 1765	EXAMINER Powell, W
**APPLICANTS: Beetz Charles; Boerstler Robert;					
**CONTINUING DATA VERIFIED: THIS APPLN CLAIMS BENEFIT OF 60/242,726 10/24/2000					
** FOREIGN APPLICATIONS VERIFIED:					
PG-PUB		DO NOT PUBLISH <input type="checkbox"/>		RESCIND <input type="checkbox"/>	
Foreign priority claimed		<input type="checkbox"/> yes <input type="checkbox"/> no		ATTORNEY DOCKET NO	
35 USC 119 conditions met		<input type="checkbox"/> yes <input type="checkbox"/> no		NANO 3.0-007	
Verified and Acknowledged Examiners's initials					
TITLE : Process for producing macroscopic cavities beneath the surface of a silicon wafer					
U.S. DEPT. OF COMM./PAT. & TM.-PTO-435L (Rev. 12-94)					

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NOTICE OF ALLOWANCE MAILED		CLAIMS ALLOWED	
		Total Claims	Print Claim for 0.0
Assistant Examiner		DRAWING	
		Sheets Drawg.	Figs. Drawg.
Primary Examiner		Print Fig.	
<input type="checkbox"/> TERMINAL DISCLAIMER		Application Examiner	
PREPARED FOR ISSUE			
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